L Number	Hits	Search Text	DB	Time stamp
1	75478	438/$.ccls.	USPAT; US-PGPUB	2004/03/11 18:15
2	536100	semiconductor or ic or "integrated circuit" or microelectronic	USPAT; US-PGPUB	2004/03/11 18:15
3	1	("6555401").PN.	USPAT; US-PGPUB	2004/03/11 18:15
4	135502	polish$3	USPAT; US-PGPUB	2004/03/11 18:15
5	134806	rins$3	USPAT; US-PGPUB	2004/03/11 18:15
6	2045	polish$3 with rins$3	USPAT; US-PGPUB	2004/03/11 18:15
7	536100	semiconductor or ic or "integrated circuit" or microelectronic	USPAT; US-PGPUB	2004/03/11 18:15
8	1083	(polish$3 with rins$3) and (semiconductor or ic or "integrated circuit" or microelectronic)	USPAT; US-PGPUB	2004/03/11 18:15
9	636181	gradual or gradually or transition	USPAT; US-PGPUB	2004/03/11 18:15
10	38	(polish$3 with rins$3) with (gradual or gradually or transition)	USPAT; US-PGPUB	2004/03/11 18:15
11	37	(semiconductor or ic or "integrated circuit" or microelectronic) and ((polish$3 with rins$3) with (gradual or gradually or transition))	USPAT; US-PGPUB	2004/03/11 18:16

C:\APPS\EAST\Bin\joannie rinse polish.wsp

Drafts

Pending

Active

L1: (13932) (polish$ or CMP) with (rins$ or clean$)

L2: (1384584) metal or metals

L3: (1198) 1 with 2

L4: (75478) 438/$7.ccls.

L5: (213) 3 and 4

L6: (2978221) @ad<19991231

L7: (76) 5 and 6

L8: (1) ("5876271").PN.

L9: (86221) H2O2 or hydrogenperoxide or "hydrogen peroxide" or "hydrogen-peroxide" or "H.sub.2O....

Failed

Saved

Favorites

Tagged (0)

UDC

Queue

Trash

U	Document	Issue Da	Pag	Title	Current	Current X	Retrieval	Inventor	S	C	P		